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⌘ Title: **JP2000345041A2: COMPOSITION FOR FORMING FILM, PRODUCTIC  
COMPOSITION FOR FORMING FILM, AND MATERIAL FOR FORMINI  
INSULATION FILM**

⌘ Derwent Title: Composition for film formation for production of semiconductors,  
comprises a product of hydrolysis and condensation obtained by  
hydrolyzing and condensing organosilicon compound(s) [\[Derwent Record\]](#)

⌘ Country: **JP Japan**⌘ Kind: **A2 Document Laid open to Public inspection i**

⌘ Inventor: **NISHIKAWA MICHINORI;  
TSUNODA MAYUMI;  
INOUE YASUTAKE;  
YAMADA KINJI;**

⌘ Assignee: **JSR CORP**  
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⌘ Published / Filed: **2000-12-12 / 1999-06-04**

⌘ Application **JP1999000158674**  
Number:

⌘ IPC Code: **C08L 83/04; C08K 5/06; H01L 21/312; H01L 21/316;**⌘ Priority Number: **1999-06-04 JP1999000158674**

⌘ Abstract: **PROBLEM TO BE SOLVED:** To obtain a composition having improved storage stability and giving a film improved in uniformity, permittivity, and leak current characteristics by selecting a composition containing a hydrolyzate of a silane compound or a condensate of the hydrolyzate and having a specified propylene glycol content.

**SOLUTION:** This composition contains at least either of a hydrolyzate and/or a condensate selected from a compound of formula I and a compound of formula II and a solvent of formula III of a purity of 99% (as measured by gas chromatography) and has a propylene glycol content of 10,000 ppm or below. In the formula, R1 is H, F, or a monovalent organic group; R2 to R6 are each a monovalent organic group; a, b, and c are each 0-2; R7 is O or - (CH2)n-; in formula II, n is 1-6; d is 0 or 1; R8 and R9 are each a monovalent organic group selected from H, a 1-4C alkyl, and CH3CO-; and e is 1-2. The composition desirably has an iron content and a sodium content each of which is 15 ppb or below and may contain a  $\beta$ -diketone, a compound having a polyalkylene oxide structure, or the like.

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⌘ Designated

BE DE FR GB IT NL

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⌘ Family:

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	<a href="#">US6376634</a>	2002-04-23	2000-06-02	Composition for film formation and ma insulating film formation
	<a href="#">JP2001164113A2</a>	2001-06-19	1999-12-13	COMPOSITION FOR FILM FORMATI MATERIAL FOR FORMING INSULAT
	<a href="#">JP2000345041A2</a>	2000-12-12	1999-06-04	COMPOSITION FOR FORMING FILM PRODUCTION OF COMPOSITION FO FORMING FILM, AND MATERIAL FO FORMING INSULATION FILM
	<a href="#">EP1058274B1</a>	2005-07-27	2000-05-31	Composition for film formation and ma insulating film formation
	<a href="#">EP1058274A1</a>	2000-12-06	2000-05-31	Composition for film formation and ma insulating film formation
	<a href="#">DE60021476C0</a>	2005-09-01	2000-05-31	Beschichtungszusammensetzung für c Filmherstellung und Material für isolier Schichten
6 family members shown above				

⌘ Other Abstract  
Info:CHEMABS 134(03)030163H [DERABS C2001-204180](#)[Nominate this for the Gallery...](#)
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